## Masks for X-Ray Lithography

### high resolution mask
- (e-beam lithography via KIT/IMT)
  - 2.7µm titanium
  - Smallest dimension ~0.5µm
  - Sub-µm details possible
  - Good for resist <100µm (gold height 2.2µm)
  - Ø70mm round

### low contrast mask
- Laser lithography
  - 5µm polyimid
  - 2.5µm smallest dimension
  - For up to 100µm high resist (gold height 3.2µm)
  - Ø70mm or Ø100mm

### high contrast mask
- X-ray copy of low contrast mask or high resolution mask
  - 100µm silicon
  - Smallest dimension from low contrast mask
  - For up to 200µm high resist (gold height 35µm)
  - Ø70mm or Ø100mm

### high contrast mask
- Laser lithography
  - 100µm silicon
  - 8µm smallest dimension
  - For up to 800µm high resist (gold height 25µm)
  - Ø70mm or Ø100mm

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Please contact us to receive details about the realisation of your specific mask requirements.
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